

10th IFAST WP9 meeting



Bundesministerium
für Bildung
und Forschung

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(Novel accelerator technology for efficient light sources NOVALIS)

14 Sept. 2023

Tasks at Uni Siegen

1. Deposition studies:

Nb, NbN, **NbTiN**, Nb₃Sn as well as **MgB₂** sputter-coatings on
Nb and Cu flat samples and ALD-coated flat samples

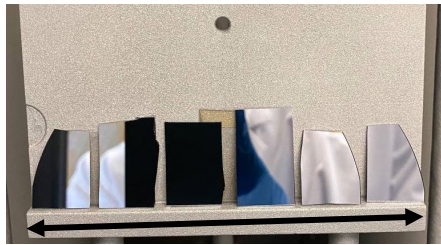
+ repair of the CC800 heater

2. Substrate preparation: **Cu** and **?Nb?** samples

3. Sample characterization: microstructure, SC and RF properties

4. Developments and upgrades

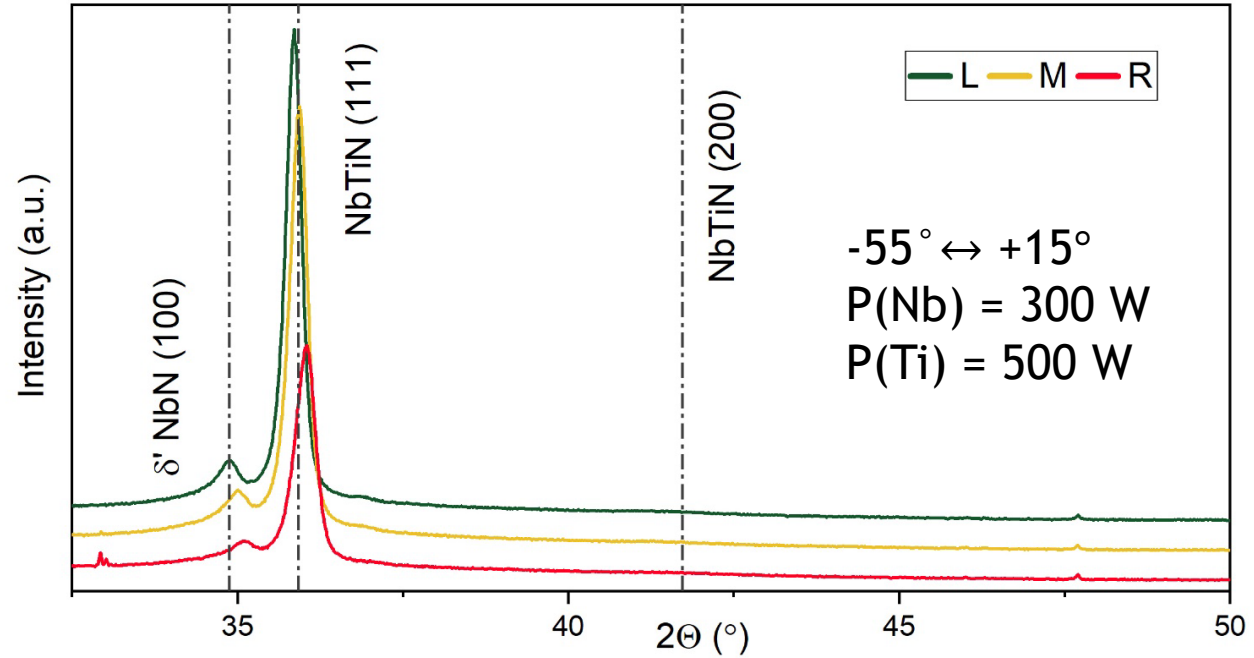
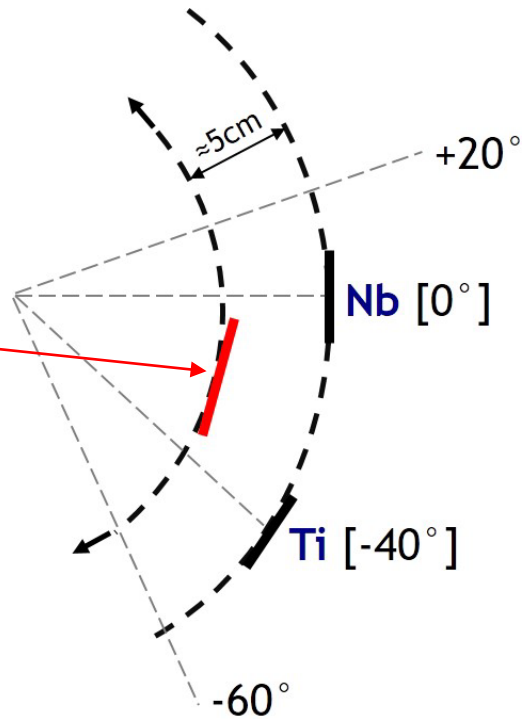
1a. co-NbTiN: rocking angle



Sample stage 120mm

Rocking angle

-60	+20
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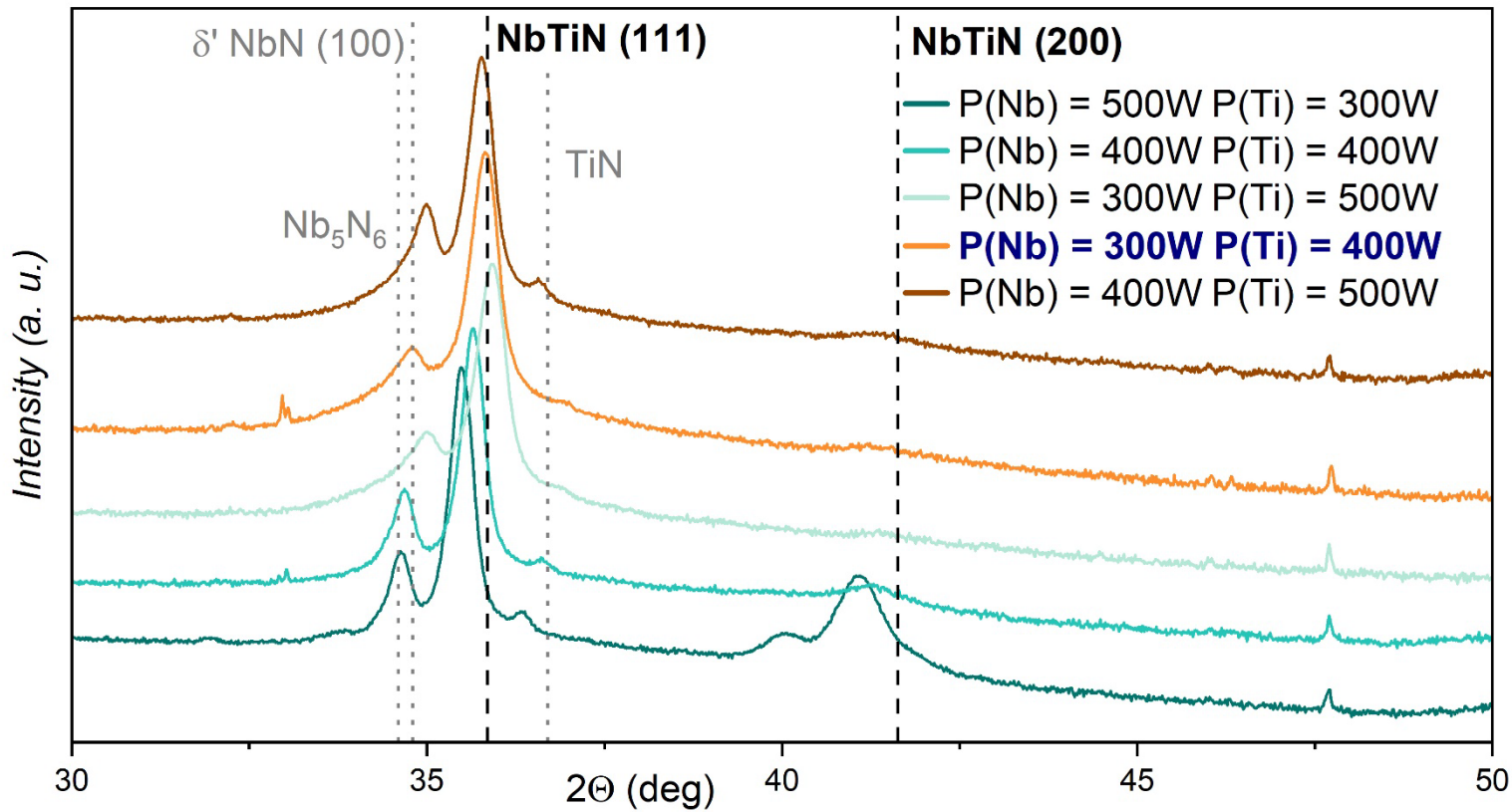


Change the Ti/Nb power ratio:

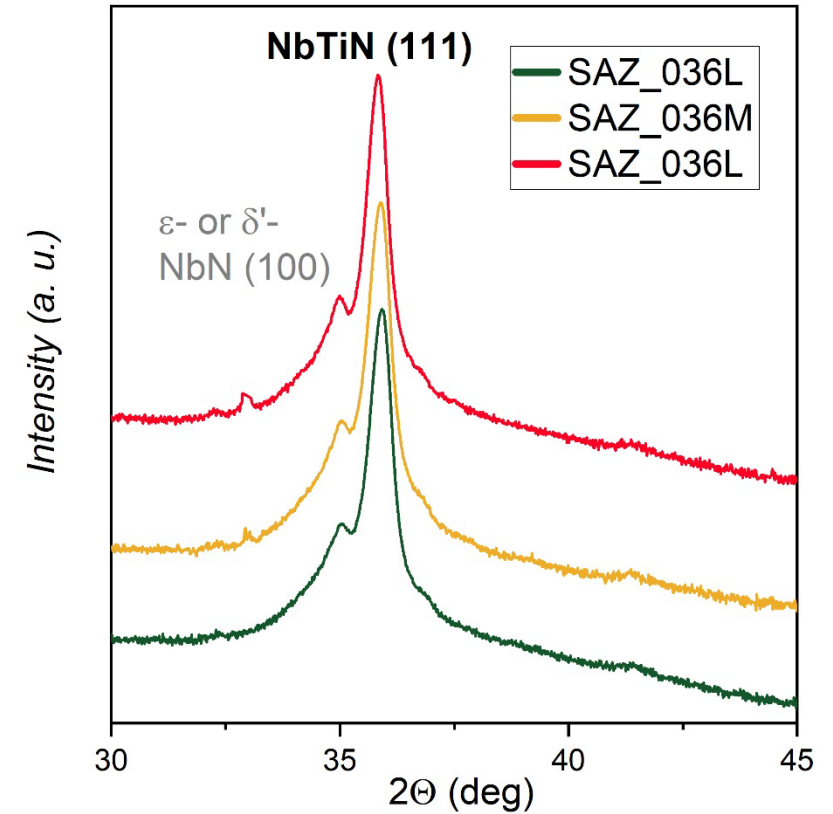
- Optimum around 500W/300W
- Rocking angle $[-60^\circ \leftrightarrow +20^\circ]$
- Needs to vary other parameters: p , Ar/N₂, bias...

1b) co-NbTiN: cathode power

Optimal? ration: $\mathcal{P}(\text{Nb}) = 300\text{W}$, $\mathcal{P}(\text{Ti}) = 400\text{W}$ [on Si(001)]

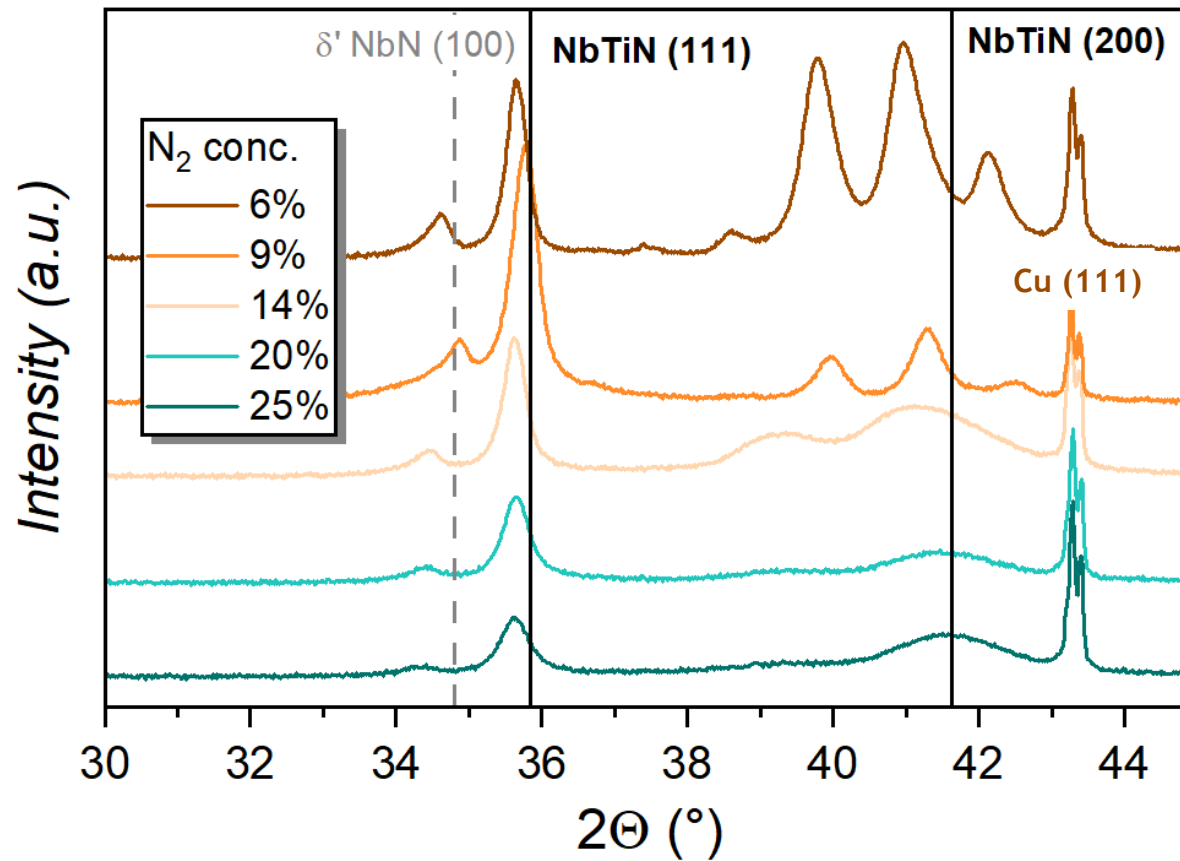


Impurity phase doesn't depend on the sample position



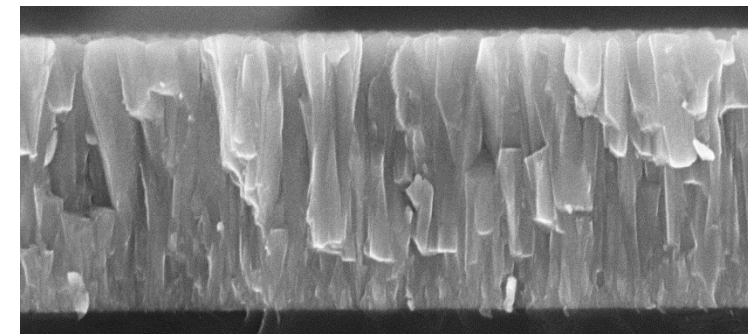
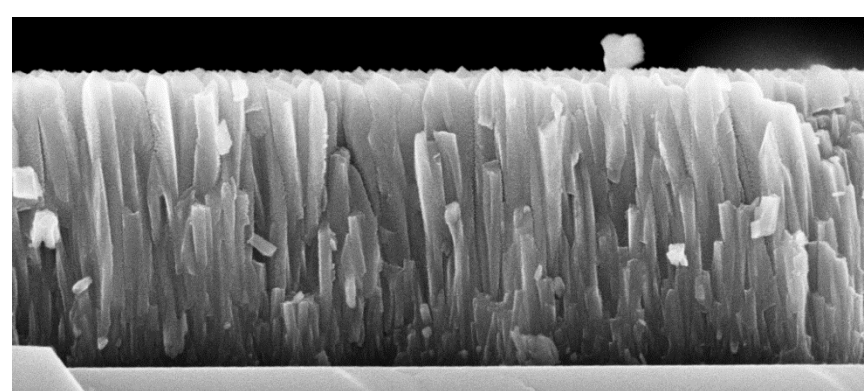
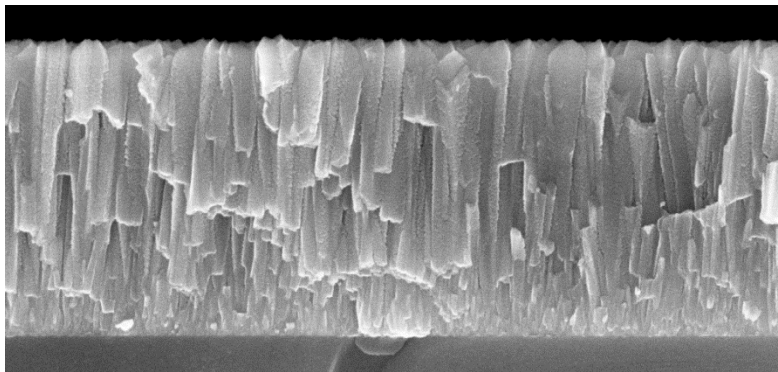
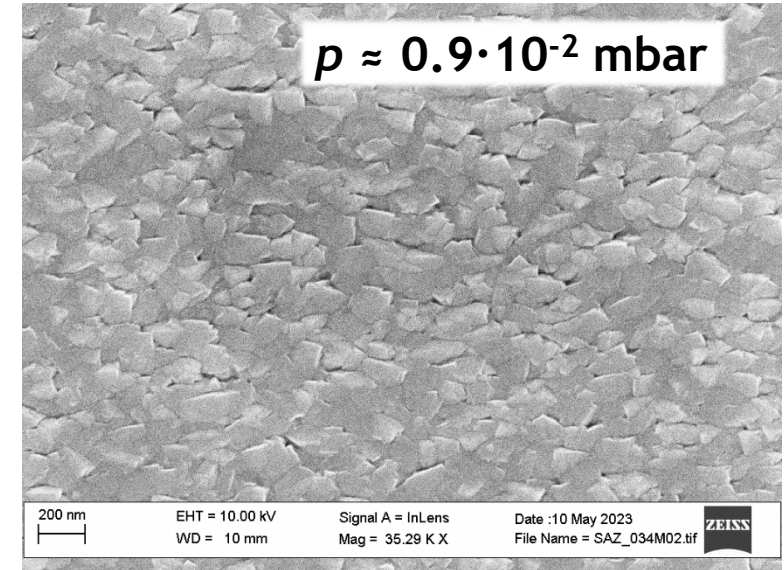
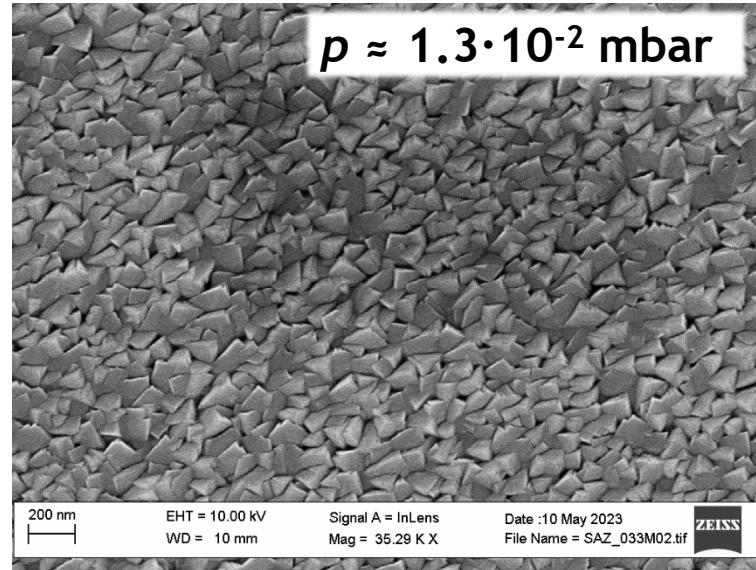
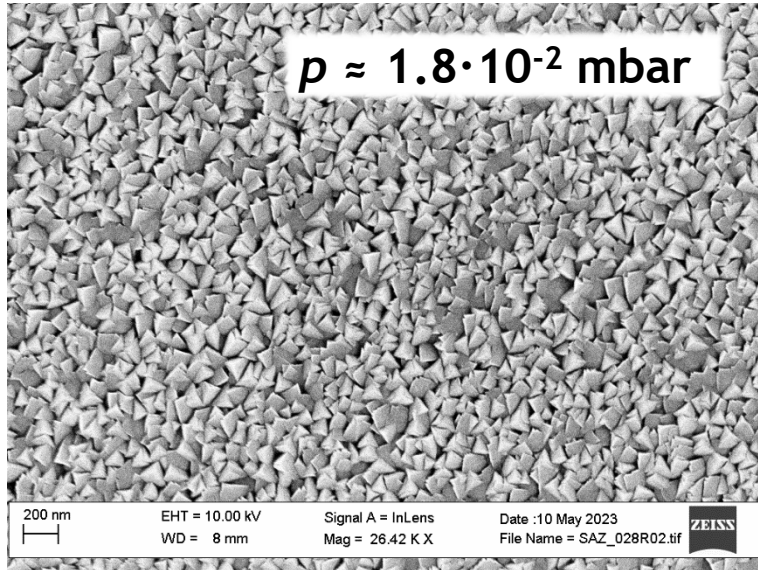
1c) co-NbTiN: N₂ concentration

$\mathcal{P}(\text{Nb}) = 300\text{W}$, $\mathcal{P}(\text{Ti}) = 400\text{W}$, $p_{\text{dep}} \approx 1.25\text{Pa}$ [on Cu]



1d) co-NbTiN: deposition pressure

$\mathcal{P}(\text{Nb}) = 300\text{W}$, $\mathcal{P}(\text{Ti}) = 500\text{W}$, 9% of N_2 [on Si(001)]



Heater repair

mid-July - end of August
a month and a half there were no coatings

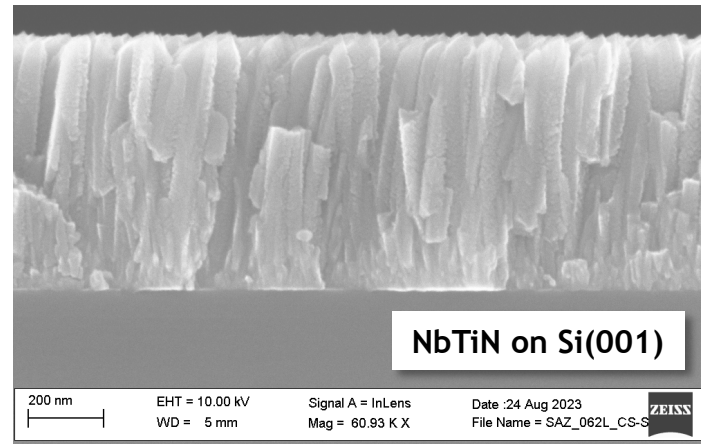
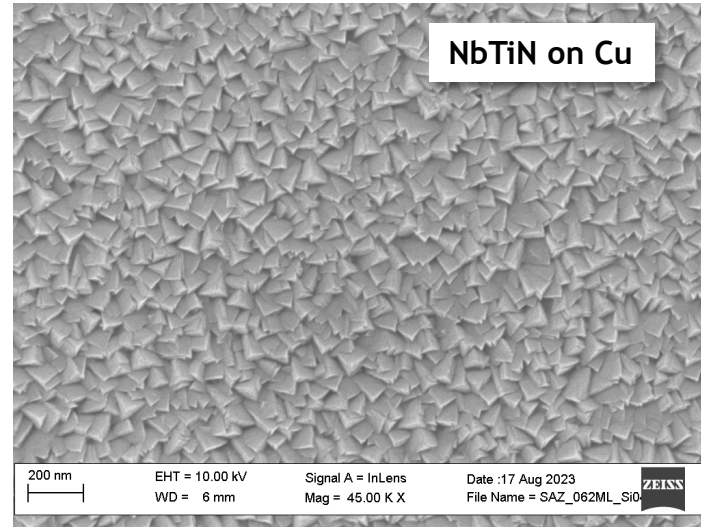
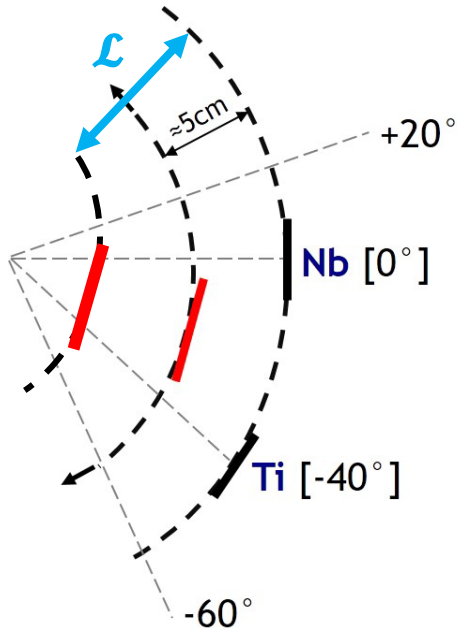


co-NbTiN: variation of parameters

Parameters	Influence
Cathode power on Nb target	Too high: delamination, NbN parasitic phases Too low: bad performance, pyramid-head columns
N ₂ concentration	> 10% better, but still not a single-phase
Pressure	Deposition at low p , but still not a single-phase

co-NbTiN: variation of parameters

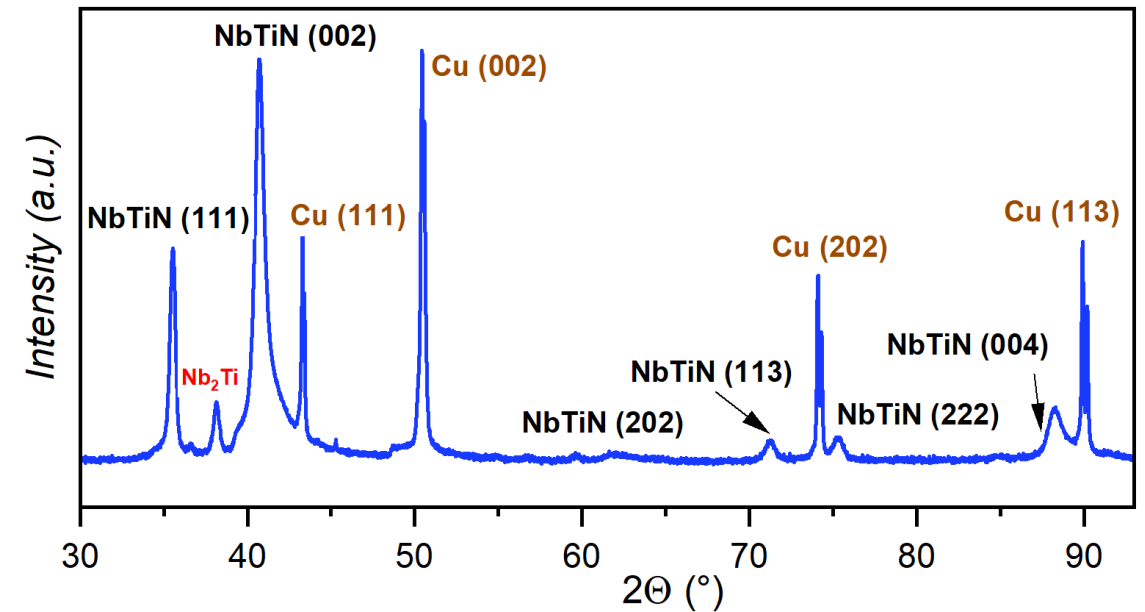
Increase
sub.-target distance \mathcal{L}



Conditions:

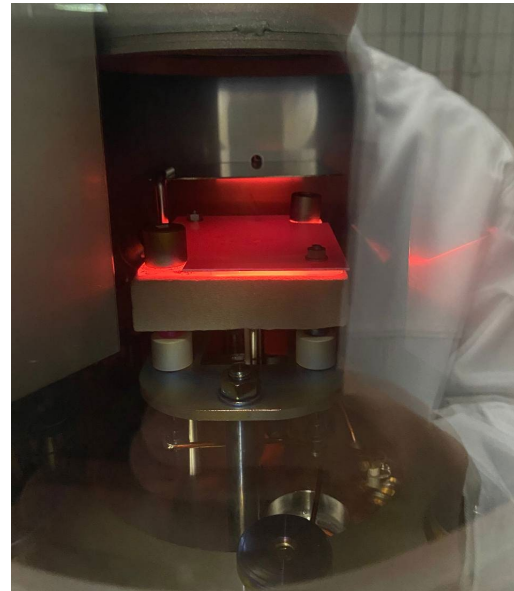
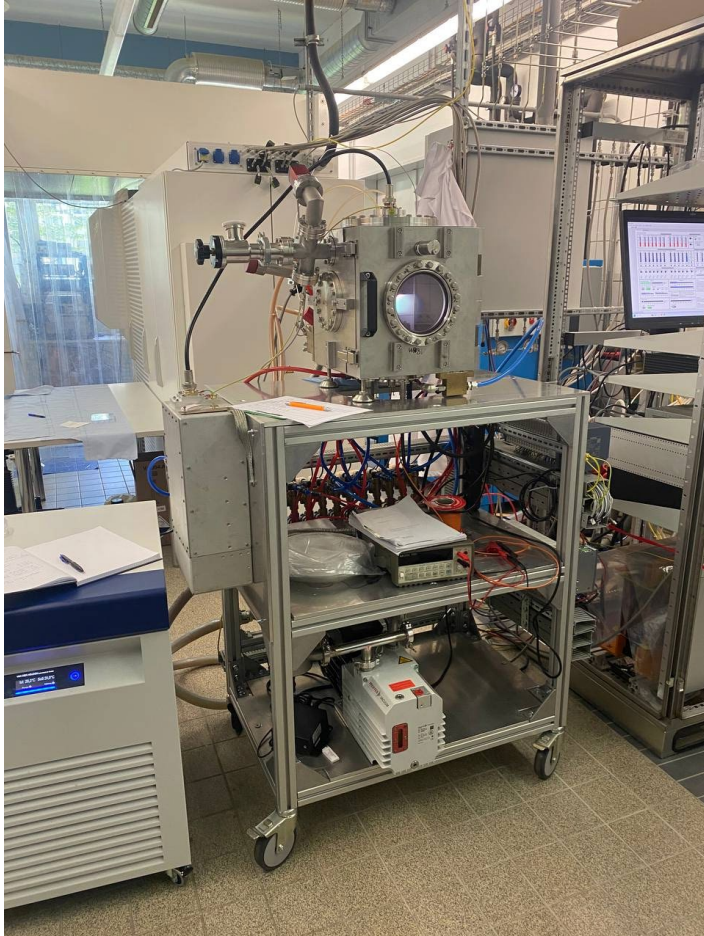
$\mathcal{P}(\text{Nb}) = 400\text{W}$, $\mathcal{P}(\text{Ti}) = 400\text{W}$, $p_{\text{dep}} \approx 1.25\text{Pa}$, 9% of N_2

$\mathcal{L} \approx 13\text{ cm}$



Film composition: Nb/Ti $\approx 0.83/0.17$

1 RF-magnetron sputtering of MgB_2



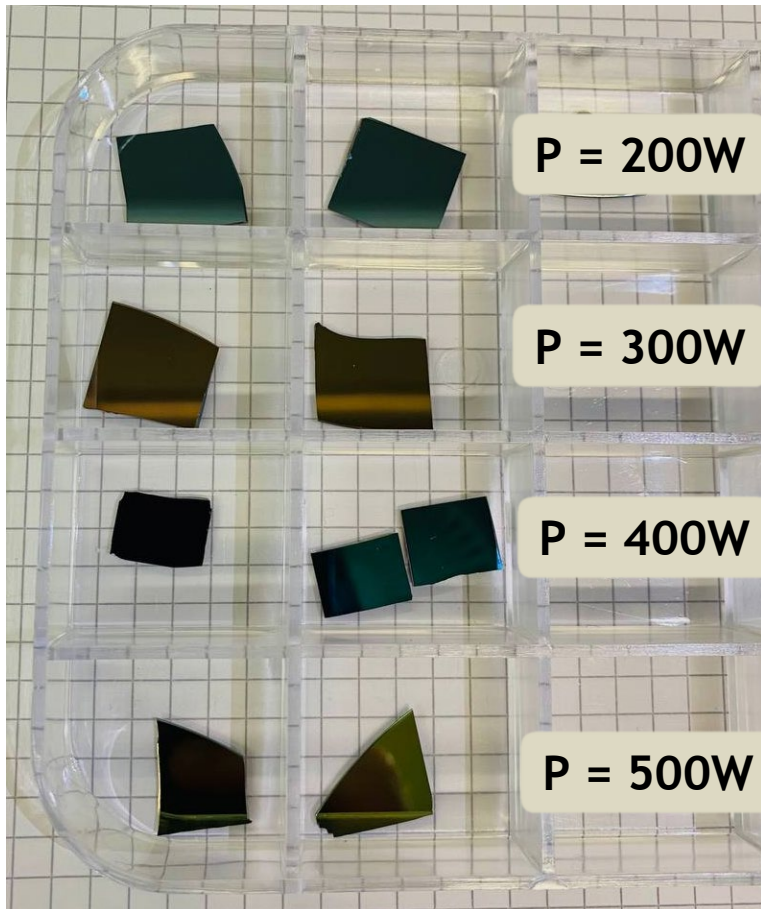
Substrate temperature up to 1500°C

BoxCoater works!!!

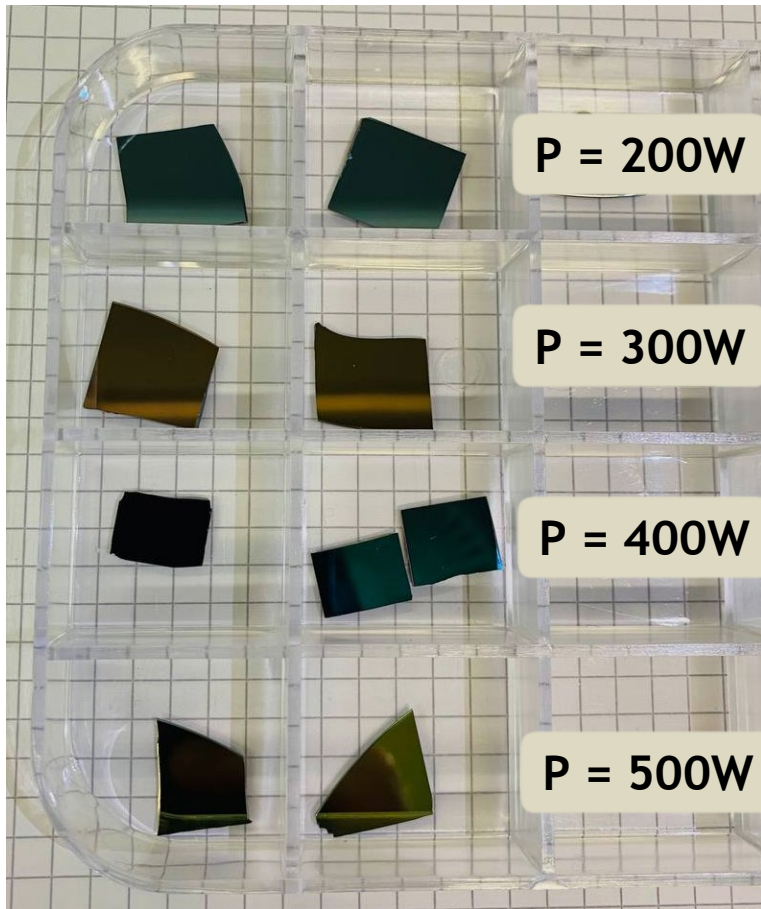
MgB_2 sputtering in Ar



1 RF-magnetron sputtering of MgB_2

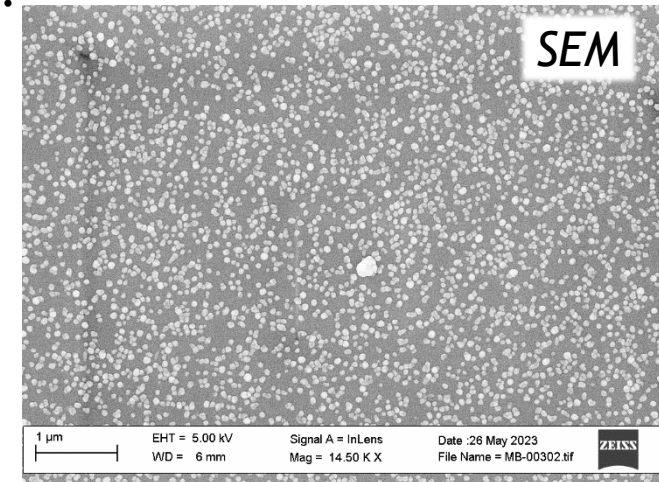
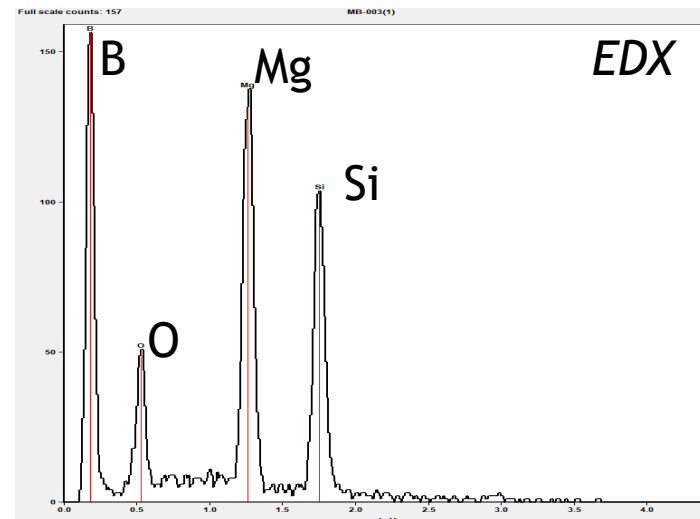
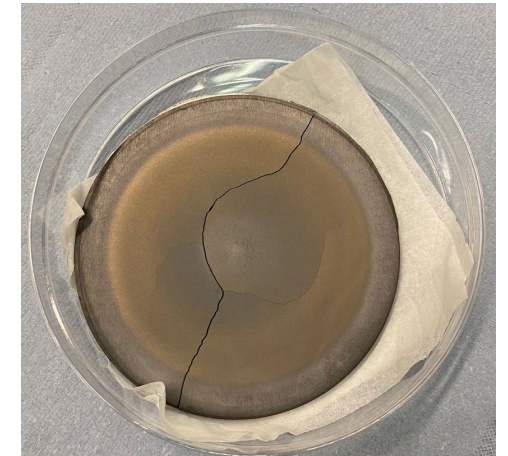


1 RF-magnetron sputtering of MgB_2

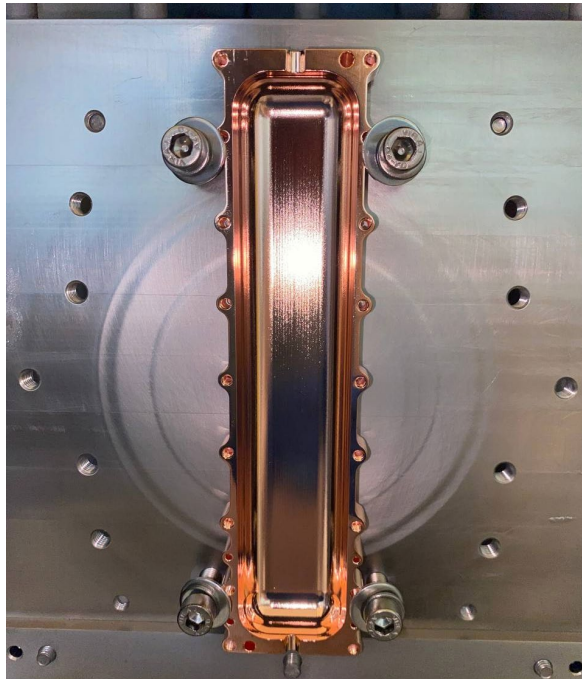


Challenges of the MgB_2 sputtering:

- Brittle material → deposition limits
- Composition ↔ Cathode power
- Oxygen contamination of the surface
- Often high Mg vapor pressure is required...

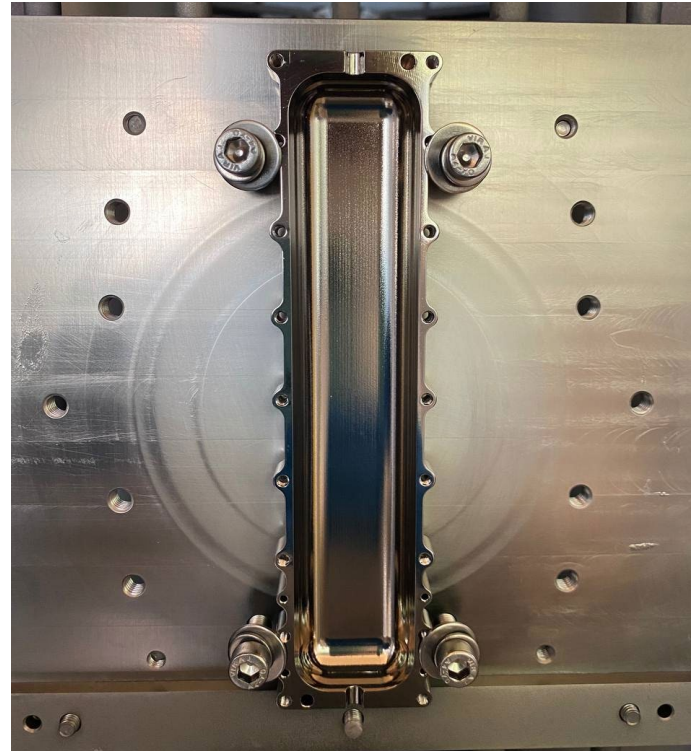


Coating of the split cavity (RASTA project)



Cu split cavity

NbN, ~2 μ m



Plans and outlook

- Co-sputtering of **NbTiN** on **Cu substrates**, tuning the deposition window, subs.-target \mathcal{L} → deposition of multilayer (SS or SIS) structures
- Plan **B**: sputtering from a single alloy **NbTi** target (already bought)
→ usage of HiPIMS or DC cathodes
- Development of **MgB₂** deposition, get at least something **crystalline**
- Characterization by XRD, SEM, AFM, SIMS, ... → good **NbTiN** films for SC properties
- Nb substrates - can be prepared outside the university

THANK YOU FOR YOUR ATTENTION!